

Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma

Thin film coating by magnetron sputtering

AC 450



by
allianceconcept

Simple and highly flexible the AC 450 guarantees success in your research activities.

Research and Development oriented equipment, **the AC450 has a variety of configurations** that will be used to design the most suitable system that matches your specifications.

Your choice will be focused on :

- Sputter up or down
- Load lock introduction : manual or motorised transfer arm
- Planar (4 x 100 mm) or convergent (3 x 100 mm) configuration
- Substrate holder cooled and/or heated (up to 800°C)
- RF, DC or DC+ power supplies for sputtering
- RF polarisation of the substrate holder for etching phases of the surface before deposition and / or bias deposition
- Dry or rotary vane rough pumping
- Turbomolecular or cryogenic secondary pumping
- Working pressure regulation (total or partial)
- Etc.



Main features

Vacuum chamber diameter :	450 mm
Height :	305 mm
Volume :	50 litres
Ultimate vacuum (turbomolecular configuration) :	5.10^{-7} mbar ^[1]
Ultimate vacuum (cryogenic configuration) :	5.10^{-8} mbar ^[1]
System throughput :	Up to 4 active 100 mm
Planar configuration uniformity :	< +/- 5% ^[1]
Convergent configuration uniformity :	< +/- 3% ^[1]
Load lock :	Yes
Fully automatic system controller :	- Process management - Traceability

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

